

REMARKS

By this Amendment, the specification and claim 2 have been amended. Reconsideration in view of the above amendments and the following remarks is respectfully requested.

In the Office Action, the Examiner has objected to the specification due to the presence of an incomplete sentence in paragraph [0002]. Applicant has amended the specification in accordance with the Examiner's recommendation and respectfully request withdrawal of the objection to the specification.

In the Office Action, the Examiner has also objected to claim 2, asserting that the term "transition" is unclear. Accordingly, in an effort to clarify claim 2, Applicant has amended claim 2 to more clearly define the light screening means. Accordingly, withdrawal of the objection to claim 2 is respectfully requested.

Claims 1-6 have been under 35 U.S.C. §103(a) as being unpatentable over Japanese Application No. 06-314352 to Nobuyoshi et al. (hereinafter "Nobuyoshi") in view of Applicants admitted prior art. This rejection is respectfully traversed.

Claim 1 recites, *inter alia*, a substrate which is moved in relation to the at least one dielectric barrier discharge lamp thereby irradiating the surface of the substrate with UV light from the at least two dielectric barrier discharge lamps, wherein a length for the at least two dielectric barrier discharge lamps in the lengthwise direction is less than a length of the transport direction of the substrate, a first area of the substrate which has been irradiated by one dielectric barrier discharge lamp and a second area of the substrate has been irradiated by another dielectric barrier discharge lamp, such that, during moving of the substrate, the first and second areas have an overlapping portion, and a light screening means by which a transition is effected between the two lamps.

Claim 2 recites, *inter alia*, a substrate treatment device using dielectric barrier discharge lamps which are transported with respect to a substrate to be irradiated, and which irradiate the surface of this substrate with UV light comprising at least two dielectric barrier discharge lamps, wherein the length of the dielectric barrier discharge lamps in a lengthwise direction is less than a length in the direction perpendicular to the transport direction of the substrate, the barrier discharge lamps being arranged such that a first area of the substrate is irradiated by one dielectric barrier discharge lamp and a second area of the substrate is

irradiated by the other dielectric barrier discharge lamp, such that during transport of the substrate the first and second areas have an overlapping portion.

Applicant respectfully submits that Nobuyoshi is entirely silent regarding a substrate which is moved in relation to the at least two dielectric barrier discharge lamps as recited in claim 1. Likewise Nobuyoshi fails to teach, suggest or disclose using dielectric barrier discharge lamps which are transported with respect to a substrate as recited in claim 2.

As is evident from Fig. 1 of Nobuyoshi, the three lamps 1A, 1B and 1C are arranged in a rectangular plane with the three lamp ends facing one side of the plane and the three opposite ends facing the other side of the plane. However, Applicant respectfully submits that this arrangement is unsuitable for enlarging the width of the irradiation area for a work piece which is transported underneath the lamps while being irradiated. Accordingly, Nobuyoshi at least fails to teach, suggest or disclose a work piece being irradiated while it is transported. Furthermore, while Applicant agrees with the Examiner that the lamps disclosed by Nobuyoshi are close enough that the light of each lamp overlaps with the light of neighboring lamps, It is pointed out that Nobuyoshi at least fails to teach, suggest or disclose a light screening means for screening part of the UV light irradiated onto the overlapping portion. In contrast, in Nobuyoshi, the light reflecting plates 11, 13 in Fig. 1 and 31, 33 in Fig. 2 that are provided between the dielectric barrier discharge lamps are provided to avoid the absorption or disturbance of light by the metal network electrodes. (see paragraph 6 of Nobuyoshi). Furthermore, as clearly described in paragraph 19 of Nobuyoshi, the light reflecting plates 11, 13, reflect the light which is normally absorbed or disturbed by the metal network of the neighboring lamps into the direction of the optical ejection aperture 20. In other words, the reflecting plates of Nobuyoshi *increase* the amount of the UV light emitted from the lamps.

In contrast, and as discussed in accordance with an exemplary embodiment of the present invention, the light screening means screens part of the UV light emitted by the lamps. In other words, the screening means *reduces* the amount of UV light, whereas the reflecting means of Nobuyoshi *increases* the amount of UV light in the overlapping area. Consequently, Applicant respectfully submits the screening means as claimed is clearly different from the reflecting means disclosed by Nobuyoshi.

Furthermore, Applicant respectfully submits the discussion and the description of

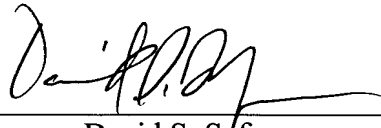
related art fails to overcome the deficiencies as noted above because traditionally the arts of speech recognition and speech synthesis were unrelated to the field of hearing aids.

Accordingly, Applicant respectfully submits that since the cited references, used either alone or in combination, fail to teach, suggest or disclose all of feature of the claims, claims 1 and 2 are neither anticipated nor rendered obvious thereby. Furthermore, since claims 3-6 depend directly or indirectly from claims 1 and 2, they should be found to be patentable for the same reasons as indicated above relative to claims 1 and 2. and in view of the additional feature(s) recited therein. Therefore, withdrawal of the rejection of claims 1-6 under 35 U.S.C. §103(a) is respectfully requested.

Applicant respectfully submits that the application is in condition for allowance. Favorable reconsideration and prompt allowance are respectfully requested.

Should the Examiner believe anything further is desirable in order to place the application in even better condition for allowance, the Examiner is encouraged to contact Applicant's undersigned representative at the telephone number listed below.

Respectfully submitted,



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